# BULLKID: KIDs Research and Developement

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### Device fabrication in Grenoble (PTA Cleanroom)



0.84

0.86

0.88

Fabrication

Robustness: feedline improvements

A wider coplanar waveguide is more resistant to defects -> **higher yield** 





### Capacitive coupling: meander no longer overlaps grooves



Optimization of the KID responsivity



### Optimization of the KID responsivity: lpha



Base design: 60nm Al  $\alpha = 5\%$ Q around 100k  $\Delta_0 = 1.880 \cdot 10^{-4} eV$ KID Volume:  $4mm^2 \times 60nm =$  $2.4 \cdot 10^5 \mu m^3$ To increase  $\frac{L_k}{L_k + L_{MAG}}$  we can Tune the geometry to reduce  $L_{MAG}$ Tune the metallic layer to increase  $L_k$ 

Optimization of the KID responsivity:  $\alpha$  – AlTiAl trilayer

Al 14 nm / Ti 33 nm / Al 30 nm  $T_c = (835 \pm 5) \text{ mK}; \Delta_0 = 1.266 \cdot 10^{-4} eV$ 

$$\Delta(T_{\text{low}}) \approx \Delta_0 \cdot e^{-\sqrt{2\pi k_B T / \Delta_0} \cdot e^{-\Delta_0 / k_B T}}$$



$$\frac{\delta f}{f_0} = -\frac{\alpha}{2} S_2(\omega, T) \frac{\delta n_{qp}}{2N_0 \Delta}$$

Fit for  $\alpha$  with  $\Delta_0$  fixed: •  $\alpha = 24\%$ (Cardani2018 reports  $\alpha = 17\%$  and  $T_c = 805$  mK) Optimization of the KID responsivity:  $\alpha$  – AlTiAl trilayer



Optimization of the KID responsivity:  $\alpha$  – 30nm AI (Thin wafer)

 $T_c = 1.4 \text{ K} \rightarrow \Delta_0 = 2.12 \cdot 10^{-4} eV$ 



Fit for  $\alpha$  with  $\Delta_0$  fixed: •  $\alpha \approx 16\%$   $\alpha_{30nm} \approx 3 \cdot \alpha_{60nm}$   $V_{30nm} = 0.5 \cdot V_{60nm}$ However we expect  $\eta_{30nm} < \eta_{60nm}$ 

- Overall gain in  $\frac{d\phi}{dE}$
- Standard fabrication process

### Optimization of the KID responsivity: $\alpha$ – 90nm AI (STACK-02)

 $T_c = 1.2 \text{ K}$  $\Delta_0(T_c) = 1.76 \cdot k_B \cdot T_c = 1.880 \cdot 10^{-4} eV$ 



#### More resilient to defects



Fit for 
$$\alpha$$
 with  $\Delta_0$  fixed:  
•  $\alpha \approx 3.3\%$   
 $\alpha_{90nm} \approx \frac{2}{3} \cdot \alpha_{60nm}$  that  
compensates  
 $\eta_{90nm} > \eta_{60nm}$ 

### Optimization of the KID responsivity: $\alpha$ – Alternate geometries



Optimization of the KID responsivity:  $\alpha$  – Alternate geometries



### Scalability for the 100mm mask: simulations and thin wafer test



- 145 pixels
- 49.3g of active silicon per wafer
- Constant cap trimming: 8um per step
- F∈ 720 ÷ 970 MHz
- dF  $\in$  0.7  $\div$  3 MHz



### Scalability for the 100mm mask: thick wafer



Scalability for the 100mm mask: thick wafer



## Simulations of x-talk induced by proximity



#### Induced current density: 30%

#### Induced current density: 3%

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### BULLKID v7 – Al90nm cryostat with optical window



### BULLKID v7 – Sky simulator



### BULLKID v7 – Sky simulator mapping proof of concept



### KIDs on Germanium for (CEvNS and DM)



Nuclear waste monitoring

However **Ge oxide is not inert**! Qi seems promising, energy calibration is the next step

### Conclusion: next work

- Finalizing the **4 inch mask**
- Settle for an optimized pixel to achieve **lower threshold**
- Energy resolution + improved process for a germanium 4-pixel sample



(Extra) Calder-GE Pulse Decay Time



### (Extra) Pulse Rise Time



24

### (Extra) GE Noise Power Spectrum



### (Extra) BULLKID Noise Power Spectrum



### (Extra) Capacitive coupling: meander no longer overlaps grooves



### (Extra) S21 scan of bonded AlTiAl wafer



Irregular spacing, excess attenuation (circa -35 dB) Feedline likely interrupted 57 detected resonators

### (Extra) Pulse timings Al vs Al-Ti-Al



### (Extra) AlTiAl alpha estimate from frequency shift

• 
$$f_M^B = f_M^A$$
  $\alpha = \frac{L_k}{L_k + L_M} \to f_0 = \frac{1}{\sqrt{C(L_k + L_M)}}$  (1)  
•  $f_0^B = 0.84$   $f_M = \frac{1}{\sqrt{C(L_M)}}$  (2)  
•  $\alpha^A = 4.98\%$   $\left(\frac{f_0}{f_M}\right)^2 = \frac{L_M}{L_k + L_M} = 1 - \frac{L_K}{L_M + L_k} = 1 - \alpha$  (3)  
 $\frac{1 - \alpha_A}{1 - \alpha_B} = \left(\frac{f_0^A}{f_0^B}\right)^2 \cdot \left(\frac{f_M^B}{f_M^A}\right)^2$  (4)  
 $\alpha_B = 1 - (1 - \alpha_A) \cdot \left(\frac{f_0^B}{f_0^A}\right)^2 = 20.1\%$  (5)